Advanced Sensing Techniques

Lecture Material 3

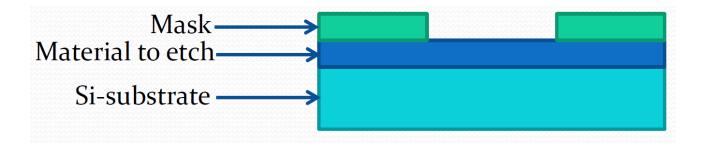
Few references:

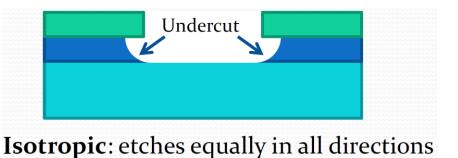
- 1. Fundamentals of Microfabrication by Marc Madou
- 2. Micro and Smart systems: G. K. Ananthsuresh et al.
- 3. Couple of Internet sources for Image illustration

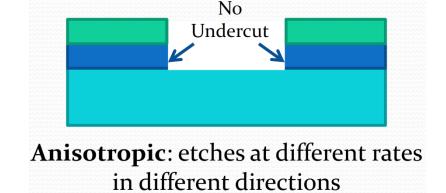
Dr. B. Mukherjee & Prof. S. Sen

Etching

- Etch: removal of material from wafer (e.g. removal silicon dioxide)
- Isotropic vs. Anisotropic
 - Isotropic— etch rate is same in all directions
 - Anisotropic— etch rate is orientation dependent







Wet Etching

- Sample is kept in etchant solution for specified amount of time
- Sample is removed from solution
- Sample is rinsed in deionized water and dried

Example Mechanism: e.g. Etchant HF, HNO3 to remove Si

hole injection: $HNO_3 + H_2O + HNO_2 \rightarrow 2HNO_2 + 2OH^-$

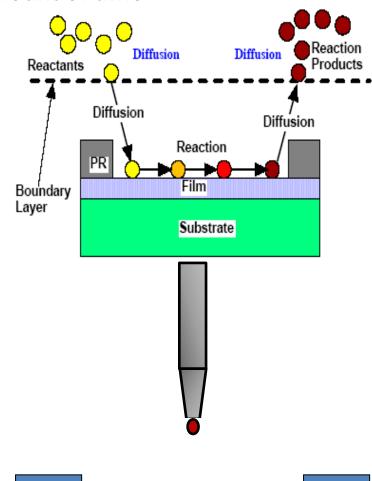
oxidation: $Si^{4+} + 4OH^{-} \rightarrow SiO_2 + H_2$

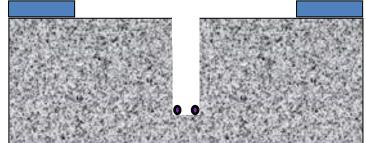
oxide removal: $SiO_2 + 6HF \rightarrow H_2 SiF_6$

Dry Etching

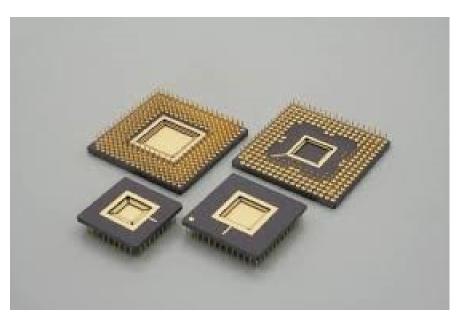
- Etchant is in gas form
- Physical & Chemical mechanism:
 - Removal based on impact, momentum transfer and chemical reaction;
 - Good material selectivity, directional control and high etch rate

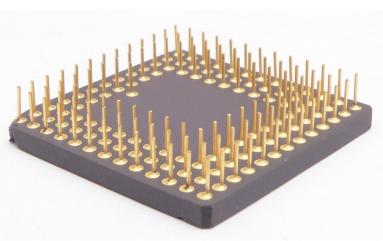
Example: Etchant Cl_2 , CCl_2 , F_2 to remove Si





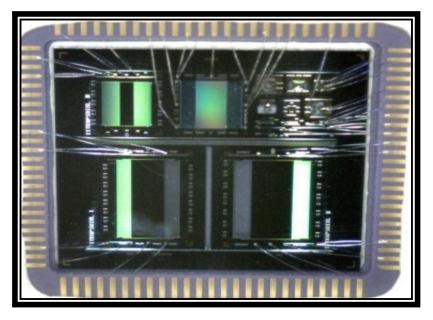
Wire Bonding and Packaging







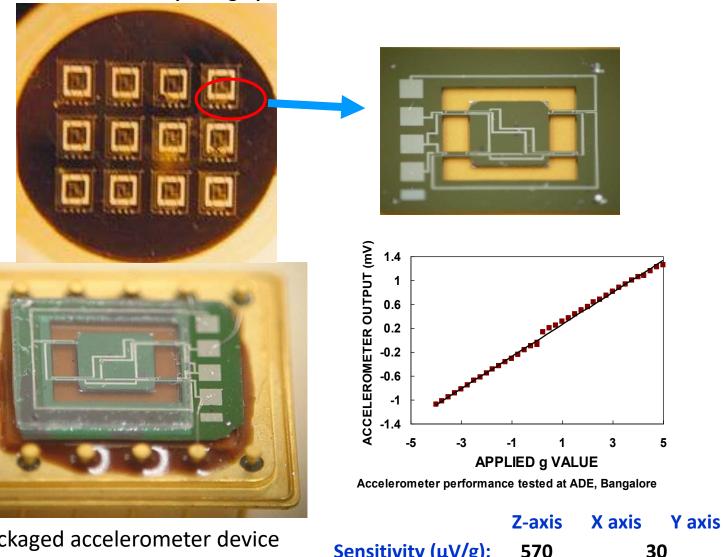
Packaging of MEMS at SCL, Chandigarh



PGA: Pin Grid Array (100 pin here)

Example: PIEZORESISTIVE SILICON ACCELEROMETER

Microphotograph of fabricated accelerometer



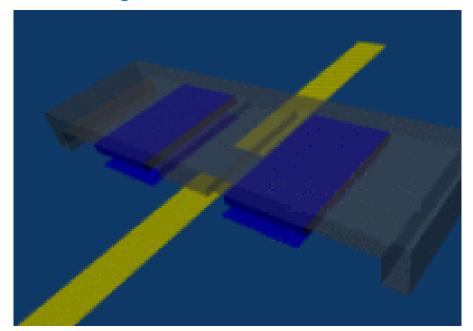
Packaged accelerometer device

Sensitivity ($\mu V/g$): 570 30 26 Linearity (%of FS): 0.19 1.5 0.63

Testing

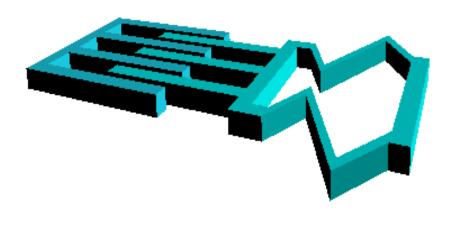
Sensing and Actuation Methods

- **❖**Electrostatic (<u>Preferable</u>)
- *Piezoelectric
- Thermal
- *Magnetic etc.



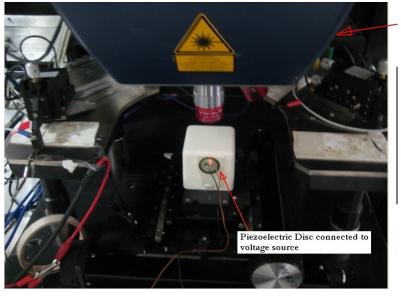
>Advantages of ES method:

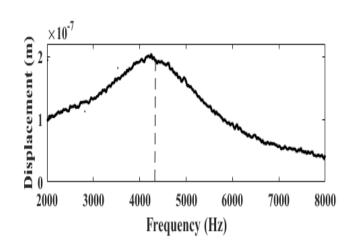
- ✓ Less resource requirement
- ✓ CMOS integration compatibility
- ✓ Large force generation
- ✓ Scalability etc.



Popular Testing Equipment

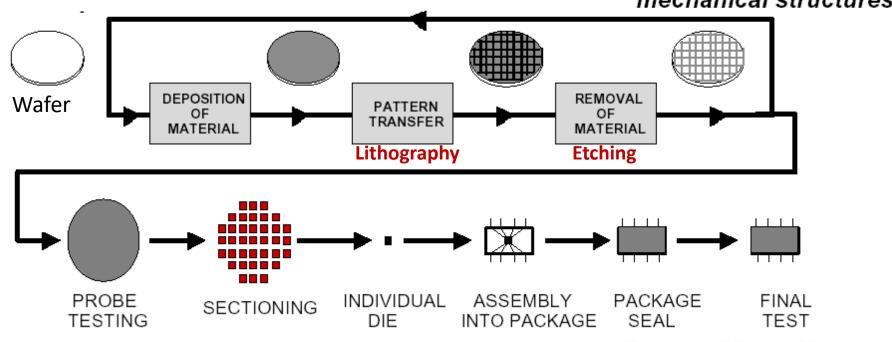






Completion of Microfabrication Process Cycle

Multiple Processing Cycles Removal of underlying materials to release mechanical structures









Accelerometers Gyro/accelerometer combo sensors

ter Pressure sensors